Date Mailed: June 26, 2007

FORM 1449* SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT	Docket Number: STFD.071US	Application Number: 10/590,223	
IN AN APPLICATION	Applicant: LIU et al.		
(Use several sheets if necessary)	Filing Date: Aug. 21, 2006	Group Art Unit: 2812	

				U.S. PATENT DOCUMENT	'S		
EXAMINER INITIAL	DOCU	MENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
/S.M./	6,897,47	1	5/24/2005	SOREF et al.			
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	DOCUMENT NO.		DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
	WO2005	/094254	13/10/2005	WIPO			
		(	OTHER DOCUM	IENTS (Including Author, Ti	tle, Date, Pertine	ent Pages, Etc.)	
/S.M./	2006	S. Balakumar <i>et al.</i> "Fabrication Aspects of Germanium on Insulator from Sputtered Ge on Si-Substrates." Electrochemical and Solid-State Letters. Vol. 9, No. 5, p. G158-G160 (2006).				n Si-Substrates."	
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EXAMINER	/Savitri Mulpuri/ (08/26/2008)	DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form for next communication to the Applicant.